

DEPOSITION APPARATUS

ABSTRACT OF THE DISCLOSURE

A deposition apparatus comprises a source unit configured to generate a plasma by arc discharge, a deposition unit in which a deposition target material is arranged so as to be irradiated with the plasma generated in the source unit, and an induction unit configured to induce the plasma for the source unit to the deposition unit. The induction unit comprises a partition unit airtightly connected to each of the source unit and the deposition unit and configured to pass the plasma inside, and a plurality of magnet units configured to form a magnetic field to induce the plasma in the partition unit. The plurality of magnet units are connected to adjust a connection angle, and the partition unit includes a tubular member bendable according to the connection angle of the plurality of magnet units.

(Figure 1)